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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of:

SABNIS, RAM W. et al.

Serial No.: 09/745,350

Filed: December 21, 2000

ORGANIC POLYMERIC  
ANTIREFLECTIVE COATINGS  
DEPOSITED BY CHEMICAL VAPOR  
DEPOSITION

Docket No.: 27710-A

Group Art Unit No.: 1756

Examiner: BARRECA, NICOLE M.

OFFICIAL

Assistant Commissioner of Patents  
Washington, D.C. 20231

Sir:

AMENDMENT

In response to the Office Action dated August 1, 2003, amendment and reconsideration of the above Application is requested.

Serial No. 09/745,350

Docket No. 27710-A

substituted and unsubstituted alkyl groups, cinnamoyl, naphthoyl, acryloyl, methacryloyl, furoyl, and thiophenecarbonyl groups; and

subjecting said antireflective compound to a chemical vapor deposition process so as to deposit said antireflective compound in a layer on said substrate surface, said antireflective compound layer deposited on said substrate surface absorbing at least about 90% of light at a wavelength of from about 150-500 nm.

2. (Original) The method of claim 1, further including the step of applying a photoresist layer to said antireflective compound layer.

3. (Original) The method of claim 1, wherein at least one of said cyclic moieties is heterocyclic or aromatic.

4. (Original) The method of claim 3, wherein said cyclic moieties are selected from the group consisting of benzene, naphthalene, anthracene, phenanthrene, pyrene, pyridine, pyridazine, pyrimidine, pyrazine, thiazole, isothiazole, oxazole, isooxazole, thiophene, furan, and pyrrole.

5. (Original) The method of claim 1, wherein the strain energy of said antireflective compound is at least about 10 kcal/mol.